

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

CHEN et al.

Atty. Ref.: 2476-37; Confirmation No. 2846

Appl. No. 10/730,381

TC/A.U. 2815

Filed: 09 December 2003

Examiner: Jackson Jr., Jerome

For: PROGRAMMABLE PHOTOLITHOGRAPHIC MASK BASED ON  
SEMICONDUCTOR NANO-PARTICLE OPTICAL MODULATORS

\* \* \* \* \*

March 23, 2009  
A Monday

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT**

Responsive to the Official Action dated December 22, 2008 (for  
which petition is hereby made for any necessary extension of time),  
please amend the above-identified application as follows: